IN THE CLAIMS:

This listing of claims will replace all prior versions, and listings, of claims in the application. Please amend claim 33 and add claim 65 according to the following listing of claims:

Claims 1-32 (cancelled)

Claim 33 (currently amended): An electrolyte for electroless deposition of metal layers with internal compressive stresses comprising a metal base salt, a reducing agent, a complexing agent, an accelerator and a stabilizer, the metal base salt comprising a metal salt whose anions are volatile~~ and that is present in a starting concentration from 0.01 to 0.30 mol/L~~.

Claim 34 (previously presented): The electrolyte of claim 33, wherein the metal salt whose anions are volatile is selected from the group consisting of metal acetate, metal formate, metal oxalate, metal nitrates, metal propionate, metal citrate, and metal ascorbate, or any combination thereof.

Claim 35 (previously presented): The electrolyte of claim 33 comprising a metal sulfate as an additional metal base salt.

Claim 36 (previously presented): The electrolyte of claim 33, wherein the reducing agent is sodium hypophosphite.

Claim 37 (previously presented): The electrolyte of claim 33, wherein the metal is nickel, copper, silver or gold.

Claim 38 (previously presented): The electrolyte of claim 33 comprising metals, copper, or finely divided particles as additional components.

Claim 39 (previously presented): The electrolyte of claim 33, wherein the complexing agent is selected from the group consisting of carboxylic acids, polycarboxylic acids, their salts, their derivatives, hydroxy(poly)carboxylic acids, 2-hydroxypropanoic acid, and propanidioic acid, or any combination thereof.

Claim 40 (previously presented): The electrolyte of claim 33, wherein the complexing agent has a concentration between 70 g/L to 90 g/L.

Claim 41 (previously presented): The electrolyte of claim 33, wherein the accelerator is a sulfur-containing heterocycle.

Claim 42 (previously presented): The electrolyte of claim 41, wherein the sulfur-containing heterocycle is selected from the group consisting of saccharine, saccharine salts, saccharine derivatives, and sodium saccharate, or any combination thereof.

Claim 43 (previously presented): The electrolyte of claim 33, wherein the stabilizer is selected from the group consisting of halogen compounds, sulfur compounds, and metals, or any combination thereof.

Claim 44 (previously presented): The electrolyte of claim 33, wherein the stabilizer is selected from the group consisting of metals, lead, bismuth, zinc, tin, and their salts whose anions are volatile, or any combination thereof.

Claim 45 (previously presented): The electrolyte of claim 44, wherein the anions that are volatile are selected from the group consisting of acetates, formate, nitrates, oxalates, propionates, citrates and ascorbates, or any combination thereof.

Claim 46 (previously presented): The electrolyte of claim 33 comprising salts or potassium iodide as additional components.

Claim 47 (previously presented): The electrolyte of claim 33 comprising:

0.01 - 0.3 M metal acetate,
30 to 50 g/L sodium hypophosphite monohydrate,
90 to 120 g/L alkaline-buffered hydroxycarboxylic acid,
0.5 to 10 g/L hydroxypolycarboxylic acid,
2.5 to 22 g/L saccharate,
0.1 to 2 g/L potassium iodide, and
0.3 to 1.5 mg/L lead acetate.

Claim 48 (previously presented): A method for electroless deposition of nickel layers with internal compressive stresses from an electrolyte comprising a metal base salt, a reducing agent, a complexing agent, an accelerator, and a stabilizer; the method comprising depositing uniform metal layers at a steady high deposition rate of 7 to 12 μm/h with a throughput of 14 to 22 MTO = 70 to 110 g metal/L; the metal base salt of the electrolyte being a metal salt whose anions are volatile and having an initial concentration of 0.048 to 0.105 mol/L.

Claim 49 (previously presented): The method of claim 48, wherein the metal salts whose anions are volatile is selected from the group consisting of the acetates, formates, oxalates, propionates, citrates or ascorbates, or any combination thereof.

Claim 50 (previously presented): The method of claim 48, wherein the metal is selected from the group consisting of nickel, copper, silver or gold.

Claim 51 (previously presented): The method of claim 48, wherein a makeup solution is added to the electrolyte while practicing the method.

Claim 52 (previously presented): The method of claim 51, wherein the makeup solution comprises a reducing agent, an alkaline-buffered complexing agent, and an accelerator.

Claim 53 (previously presented): The method of claim 51, wherein a second makeup solution is added to the electrolyte while practicing the method.

Claim 54 (previously presented): The method of claim 53, wherein the second makeup solution comprises a nickel base salt, a complexing agent, an accelerator, and a stabilizer.

Claim 55 (previously presented): The method of claim 48, the method being carried out with a closed material circulation.

Claim 56 (previously presented): The method of claim 48, the method being used to co-deposit additional materials, the additional materials being selected from the group consisting of phosphorus, metals, cobalt, and finely divided particles, or any combination thereof.

Claim 57 (previously presented): The method of claim 56, the method being used to deposit metal-phosphorus layers with phosphorus contents >10%.

Claim 58 (previously presented): The method of claim 56, the method being used to deposit metal-phosphorus layers with phosphorus contents from 2-10%, and wherein electrolyte has a pH between 4.6-6.2.

Claim 59 (previously presented): The method of claim 48, wherein the reducing agent is sodium hypophosphite.

Claim 60 (previously presented): The method of claim 48, wherein the complexing agent is selected from the group consisting of carboxylic acids, polycarboxylic acids, their salts, their derivatives, hydroxy(poly)carboxylic acids, 2-hydroxypropanoic acid, and propandioic acid, or any combination thereof.

Claim 61 (previously presented): The method of claim 48, wherein the complexing agent has a concentration between 70 g/L to 90 g/L.

Claim 62 (previously presented): The method of claim 48, wherein the accelerator is a sulfur-containing heterocycle.

Claim 63 (previously presented): The method of claim 62, wherein the sulfur-containing heterocycle is selected from the group consisting of saccharine, saccharine salts, saccharine derivatives, and sodium saccharate, or any combination thereof.

Claim 64 (previously presented): The method of claim 48, wherein the electrolyte is regenerated by means of electrodialysis or ion exchange resins, or a combination thereof.

Claim 65 (new): The electrolyte of claim 33, wherein the metal base salt comprising a metal salt whose anions are volatile is present in a starting concentration from 0.01 to 0.30 mol/L.